

<b>Notice of References Cited</b>	Application/Control No. 09/838,513	Applicant(s)/Patent Under Reexamination CHEN ET AL.	
	Examiner Julio J. Maldonado	Art Unit 2823	Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,937,325	08-1999	Ishida, Emi	438/655
*	B	US-6,514,859 B1	02-2003	Erhardt et al.	438/664
	C	US-			
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	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
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**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Mouroux, Alette; The Reactive Formation of TiSi <sub>2</sub> in the Presence of Refractory Metals (from V to W), Royal Institute of Technology, Department of Electronics, Stockholm 1,999.
	V	
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	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.